

AMENDMENTS TO THE SPECIFICATION

At page 2, lines 27-28, amend the paragraph as follows:

A1 This problem is solved with the method and the apparatus according to the ~~valid Patent Claims 1 and 8 appended claims~~. Expedient embodiments are the subject matters of the dependent claims.

At page 6, lines 1-10, amend the paragraph as follows:

A2 The receiving means ~~12~~ 5 for accommodating wafers is formed by a rotary sample plate which receives several wafers in a star-shaped arrangement. In the present case, this rotary plate has a diameter of roughly 40 cm and can be rotated at a speed of 1 to 5 min<sup>-1</sup> approximately. The rotating speed is equally predetermined by the controller unit 8. A speed of less than 5 min<sup>-1</sup> is preferably selected in order to prevent the photo resist from spreading due to centrifugal forces. The rotary movement is created by the motor 11. The spacing of the IR radiation source from the rotary plate corresponds to 20 cm approximately in the present case. The rotation of the wafers under the radiation source expediently induces a homogeneous ~~drying~~ drying of the layers provided on the wafers, with the possibility to dry several wafers at the same time.